

	Type	L #	Hits	Search Text
1	BRS	L1	711	(rinse adj5 bath or rinsing or rinse or rinsed) adj10 (displacement or displac\$4)
2	BRS	L2	12382	(SPM or sulfuric adj5 hydrogen adj5 peroxide) or ("H2SO4" or "H.sub.2SO.sub.4") adj5 ("H2O2" or "H.sub.2O.sub.2") or piranha or standard-wet
3	BRS	L3	8052	(HPM or hydrochloric adj5 hydrogen adj5 peroxide or "HCl" adj5 ("H2O2" or "H.sub.2O.sub.2") or hydrochloric adj5 peroxide or "SC-2" or "standard adj3 clean\$3 adj3 2" or "SC2")
4	BRS	L4	10955	(APM or ammonia adj3 peroxide or ("NH4OH" or "NH.sub.4OH") adj4 ("H2O2" or "H.sub.2O.sub.2" or "SC-1" or "standard adj5 clean\$3 adj5 1" or "SC1"))
5	BRS	L5	1004	(L2 or L3) same L4
6	BRS	L6	17	15 and 11
7	BRS	L7	13	16 and (cascad\$ or overflow\$)
8	BRS	L8	4385	(rinse adj5 bath or rinsing or rinse or rinsed) same (displacement or displac\$4)
9	BRS	L9	32	15 and 18

	DBs	Time Stamp	Comments	Error Definition
1	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	2005/02/08 12:57		
2	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	2005/02/08 12:53		
3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	2005/02/08 12:53		
4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	2005/02/08 12:53		
5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	2005/02/08 12:54		
6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	2005/02/08 12:55		
7	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	2005/02/08 12:57		
8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	2005/02/08 12:57		
9	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	2005/02/08 12:57		

	Type	L #	Hits	Search Text	DBs
1	BRS	L1	60336	(clean or cleaning or cleaned or cleaner or cleansed or cleansing or cleanse or cleanser) adj10 (substrate or semiconductor or wafer or workpiece or liquid adj3 crystal or glass adj3 substrate)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
2	BRS	L2	326565	(clean or cleaning or cleaned or cleaner or cleansed or cleansing or cleanse or cleanser or wash or washing or washed or rinse or rinsing or rinsed or treat or treating or treated or treatment of strip or stripping or stripped or stripper or etch or etching or etchant or etched) adj10 (substrate or semiconductor or wafer or workpiece or liquid adj3 crystal or glass adj3 substrate)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
3	BRS	L3	10870	(SPM or sulfuric adj5 hydrogen adj5 peroxide)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T

	Type	L #	Hits	Search Text	DBs
4	BRS	L4	3033	(HPM or hydrochloric adj5 hydrogen adj5 peroxide or "HCl" adj5 ("H2O2" or "H.sub.2O.sub.2"))	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
5	BRS	L5	11639	(SPM or sulfuric adj5 hydrogen adj5 peroxide) or ("H2SO4" or "H.sub.2SO.sub.4") adj5 ("H2O2" or "H.sub.2O.sub.2")	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
6	BRS	L6	431	14 same 15	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
7	BRS	L7	142	16 same 12	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T

	Type	L #	Hits	Search Text	DBs
8	BRS	L8	50255	("134"/\$).ccls.	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
9	BRS	L9	55	17 and 18	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
10	BRS	L10	12382	(SPM or sulfuric adj5 hydrogen adj5 peroxide) or ("H2SO4" or "H.sub.2SO.sub.4") adj5 ("H2O2" or "H.sub.2O.sub.2") or piranha or standard-wet	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
11	BRS	L11	3806	(HPM or hydrochloric adj5 hydrogen adj5 peroxide or "HCl" adj5 ("H2O2" or "H.sub.2O.sub.2") or hydrochloric adj5 peroxide or "SC-2" or "standard adj3 clean\$3 adj3 2")	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T

	Type	L #	Hits	Search Text	DBs
12	BRS	L12	10955	(APM or ammonia adj3 peroxide or ("NH4OH" or "NH.sub.4OH") adj4 ("H2O2" or "H.sub.2O.sub.2" or "SC-1" or "standard adj5 clean\$3 adj5 1"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
13	BRS	L13	3705	kawaguchi-h\$.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
14	BRS	L14	11409	shimizu-y\$.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
15	BRS	L15	4	hosohata-s\$.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T

	Type	L #	Hits	Search Text	DBs
16	BRS	L16	15108	l13 or l14 or l15	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
17	BRS	L17	984	(l10 or l11) same l12	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
18	BRS	L18	374	l17 same l2	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
19	BRS	L19	2	l18 and l16	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T

	Type	L #	Hits	Search Text	DBs
20	BRS	L20	140	118 and 18	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
21	BRS	L21	721	(rinse adj5 bath or rinsing) adj10 (overflow\$3 or weir)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
22	BRS	L22	1	121 same 118	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
23	BRS	L23	13	121 and 118	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T

	Type	L #	Hits	Search Text	DBs
24	BRS	L24	1617	(rinse adj5 bath or rinsing or rinse or rinsed) adj10 (overflow\$3 or weir or casc\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT
25	BRS	L25	8052	(HPM or hydrochloric adj5 hydrogen adj5 peroxide or "HCl" adj5 ("H2O2" or "H.sub.2O.sub.2") or hydrochloric adj5 peroxide or "SC-2" or "standard adj3 clean\$3 adj3 2" or "SC2")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT
26	BRS	L26	10955	(APM or ammonia adj3 peroxide or ("NH4OH" or "NH.sub.4OH") adj4 ("H2O2" or "H.sub.2O.sub.2" or "SC-1" or "standard adj5 clean\$3 adj5 1" or "SC1"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT
27	BRS	L27	1004	(110 or 125) same 126	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT

	Type	L #	Hits	Search Text	DBs
28	BRS	L28	826	127 and 12	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
29	BRS	L29	381	127 same 12	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
30	BRS	L30	20	129 and 124	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
31	BRS	L31	55	127 and 124	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T

	Type	L #	Hits	Search Text	DBs
32	BRS	L32	2	"6743890".pn.	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
33	BRS	L33	40451	(single adj5 (tank or chamber))	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
34	BRS	L34	2	127 same 133	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
35	BRS	L35	61	127 and 133	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T

	Type	L #	Hits	Search Text	DBs
36	BRS	L36	12	135 and 124	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
37	BRS	L37	327566	((single or "one") adj5 (tank or chamber or bath))	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
38	BRS	L38	378130	((single or "one") adj5 (tank or chamber or bath or vessel))	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
39	BRS	L39	38	127 and 138 and 124	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T

	Type	L #	Hits	Search Text	DBs
40	BRS	L40	2161	(134/26 or 134/95.1).ccls.	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
41	BRS	L41	105	124 and 140	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
42	BRS	L42	12	141 and 127	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
43	BRS	L43	6	127 same 124	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T

	Type	L #	Hits	Search Text	DBs
44	BRS	L44	25490	(rinse adj5 bath or rinsing or rinse or rinsed) same (continuous or continuously or continuing or continued or continuously adj5 feed\$4)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
45	BRS	L45	69	127 and 144	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
46	BRS	L46	54	145 and 18	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T
47	BRS	L47	17	("20010047815" "4599116" "4 713119" "4778532" "5269850" "5336371" "5489557" "56456 49" "5853491" "5885901" "59 13981" "5968848" "6068000" "6074935" "6153018" "616230 2" "6228823").PN.	US- PGPUB; USPAT